

Supporting Materials for

Surface engineering of SnO₂ for improved perovskite/SnO₂ photodetectors

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EXPERIMENTS

Materials. MAI (>99.9%), PbI₂ (99.999%), CH₃COOC₂H₅ (AR), dimethyl formamide (DMF, anhydrous), dimethyl sulfoxide (DMSO, anhydrous), SnO₂ aqueous solution (3.0 wt%), (NH₄)₂WS₄.

Surface engineering of SnO₂. The surface engineering of SnO₂ was performed as follows: (NH₄)₂WS₄ was added to the SnO₂ aqueous solution at concentrations of 1.0, 2.0, and 4.0 mg/mL, and the mixture was stirred at room temperature overnight. During stirring, the surface V_{OS} of SnO₂ were passivated through the S substitution.

Preparation of MAPbI₃/SnO₂ PDs. Indium tin oxide (ITO) substrates were cleaned with acetone, ethanol, and DI water. Then, the substrates were dried with N₂ and treated with O₂ plasma for 10 min. After that, SnO₂/(NH₄)₂WS₄ aqueous solution was spin-coated on ITO, followed by annealing at 150 °C to prepare SnO₂ thin films (labeled as S-SnO₂). Finally, the perovskite precursor, which was prepared by dissolving MAI, PbI₂ and ZIF-67 into DMF/DMSO mixtures, was spin-coated on S-SnO₂, followed by a two-step annealing process ^[1]. All experiments were carried out in an atmosphere with a humidity of ~ 50%. The scheme of preparation of MAPbI₃/S-SnO₂ heterojunctions is depicted in Fig. 1a in the main text. Patterned top Au electrodes were deposited using sputtering method with a metal mask. For comparison, MAPbI₃/SnO₂ heterojunctions were prepared under identical conditions, where the SnO₂ thin films were prepared with a pure SnO₂ aqueous solution (i.e., without surface engineering treatment).

Characterization. The morphology of SnO₂ and MAPbI₃ thin films was investigated by scanning electron microscopy (SEM, JSM-7800F). The structure of MAPbI₃ thin films was investigated by X-ray diffraction (XRD, Bruker D8 with Cu K α radiation of 1.54 Å). The steady-state and transient photoluminescence (PL) spectra of MAPbI₃ thin films were characterized with a picoseconds (ps)-pulsed laser at 450 nm. The transient PL data were recorded by a ps time-correlated single photon counting technique. X-ray photoelectron spectroscopy (XPS) was performed to study the atomic electron binding energies of SnO₂ thin films. The performance of MAPbI₃/SnO₂ heterojunction PDs was characterized by a photoresponse characterization system consisting of a Xenon lamp,

an electronic shutter, an optical attenuator, a monochromator, a microscope, two probes, a Keithley 2401, and a semiconductor parameter analyzer (Keysight, B1500A). The light power of the Xenon lamp was obtained from a standard Si PD.

Density functional theory calculations. Density functional theory calculations were carried out within the Vienna ab initio simulation package. The generalized gradient approximation in the form of the Perdew-Burke-Ernzerhof (PBE) exchange-correlation functional (GGA-PBE) was employed. For the case of S doped SnO₂, SnO (110) surface with dimensions $9.73 \times 13.58 \text{ \AA}^2$ was constructed with 5 atom layers, in which 2 bottom layers were fixed at the optimized bulk positions. In each slab model, an adequately vacuum space of $> 15 \text{ \AA}$ to eliminate possible interactions between neighboring slabs. Two types of vacancy configurations were constructed: i.e., (i) O vacancy: removal of a single O atom on the SnO (110) surface; (ii) S substituting for O: S atom occupies the site of the O defect. The k-point mesh for the Brillouin zone was set as $4 \times 3 \times 1$. As for the MAPbI₃ system, four types of vacancy configurations were constructed within the $2 \times 2 \times 2$ supercell: i.e., (i) I vacancy: removal of a single I atom in the stoichiometric host cell; (ii) Pb vacancy: removal of a single Pb atom in the stoichiometric host cell; (iii) S substituting for I: a S atom occupies one I site in the stoichiometric host cell; (iv) S substituting for I with a Pb vacancy nearby: a S atom occupies one I site with a nearest Pb vacancy in the stoichiometric host cell. The structure was fully relaxed when the energy of electron self-consistent iteration was less than $1.0 \times 10^{-5} \text{ eV/atom}$ and the interatomic forces were less than 0.02 eV/\AA .

Reference

1. Lee, J. H.; Shin, D.; Rhee, R.; Yun, S.; Yeom, K. M.; Chun, D. H.; Lee, S.; Kim, D.; Yi, Y.; Noh, J. H.; Park, J. H., Band Alignment Engineering between Planar SnO₂ and Halide Perovskites via Two-Step Annealing. *J. Phys. Chem. Lett.* **2019**, *10* (21), 6545-6550.

Supporting Figures

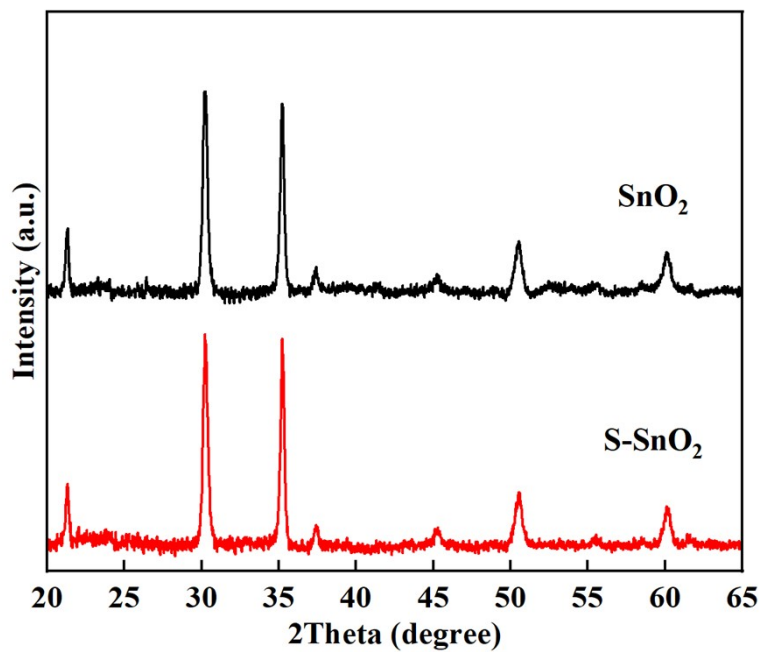


Fig. S1. XRD patterns of SnO₂ and S-SnO₂ thin films.

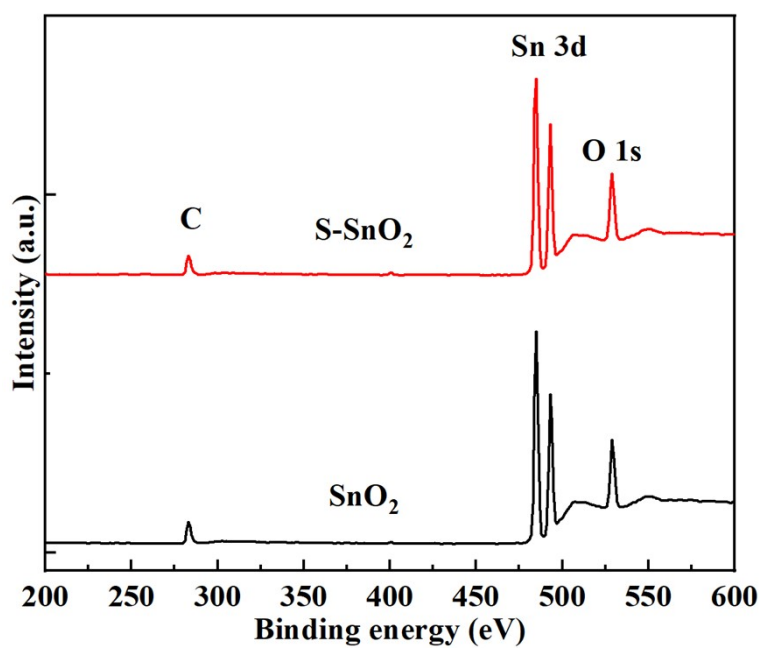


Fig. S2. XPS spectra of SnO₂ and S-SnO₂ thin films.

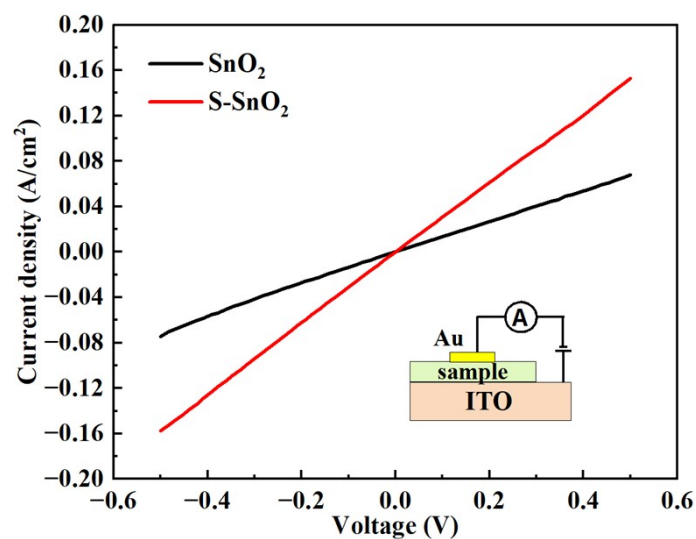


Fig. S3. I-V curves of Au/SnO₂/ITO and Au/S-SnO₂/ITO structures.

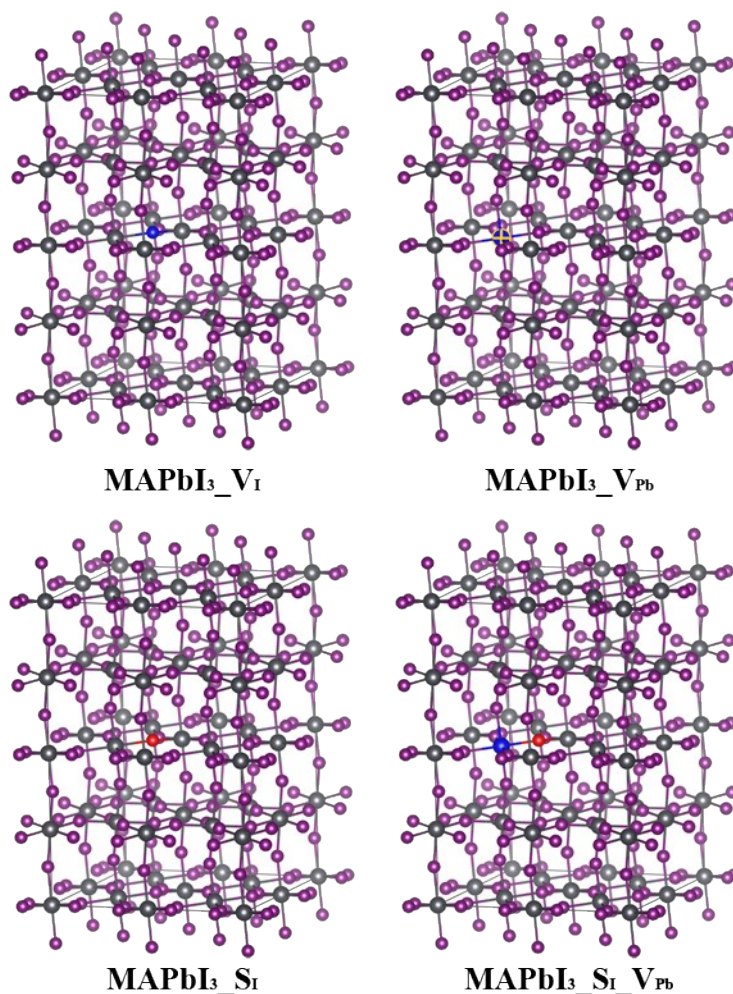


Fig. S4. Structures of MAPbI₃ supercells containing various defects. The vacancy and S substituting are labeled as blue and red spheres, respectively. The CH₃NH₃ groups are not shown herein.

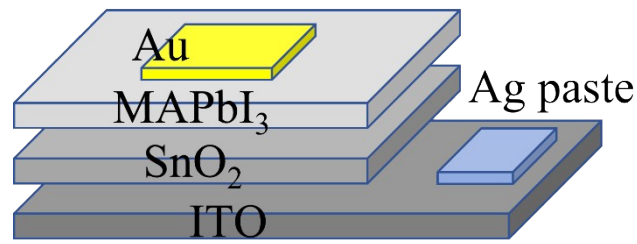


Fig. S5. Scheme of MAPbI₃/SnO₂ heterojunction PDs.

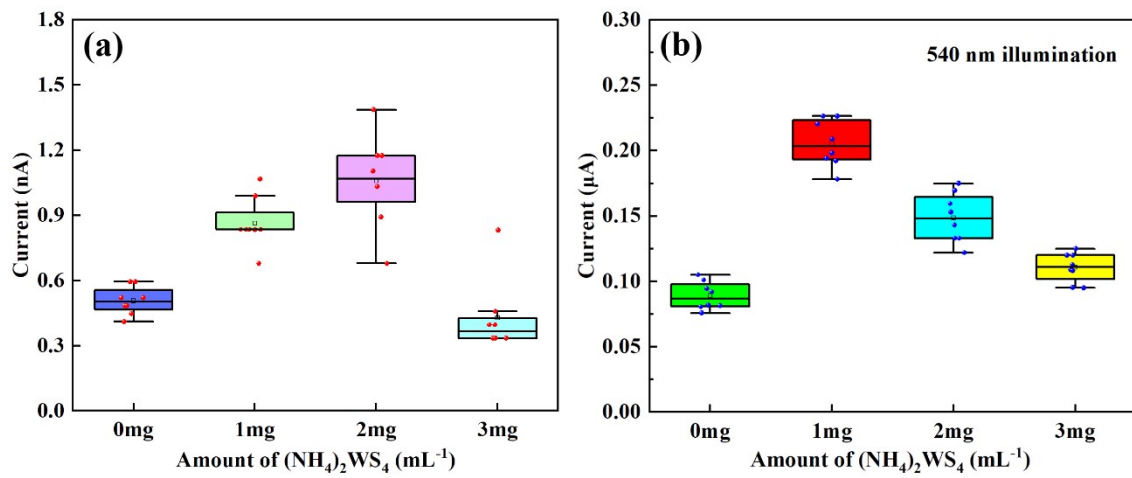


Fig. S6. Statistical results of dark current and photocurrent of MAPbI₃/SnO₂ PDs engineered with different concentrations of (NH₄)₂WS₄.

Supporting Tables

Table S1. Comparison of crystalline of MAPbI₃ thin films prepared on SnO₂ and S-SnO₂.

Crystalline plane	XRD peaks position (°)		FWHM (°)	
	On SnO ₂	On S-SnO ₂	On SnO ₂	On S-SnO ₂
020	14.16	14.16	0.0938	0.1223
002	20.06	20.06	0.1132	0.1156
031	23.54	23.54	0.1213	0.1423
220	24.56	24.54	0.1269	0.1484
040	28.50	28.48	0.1274	0.1503
230	30.26	30.30	0.3679	0.3287
141	31.94	31.92	0.1432	0.1511
321	35.26	35.24	0.3810	0.3553
400	40.72	40.70	0.1835	0.1822